SHEET 1 OF 1 SERIAL NO. ATTY, DOCKET NO. 09/363,966 004066 INFORMATION DISCLOSURE USA/Consilium/Consilium CITATION IN AN **APPLICATION** (PTO-1449) APPLICANT John F. ARACKAPARAMBIL et al. GROUP **FILING DATE** July 29, 1999 2125 U.S. PATENT DOCUMENTS FILING DATE EXAMINER'S **SUBCLASS** CLASS NAME INITIALS PATENT NO. DATE 09/29/95 08/12/97 Meikle et al. 5,655,951 451 56 5NB 05/28/96 5,823,854 10/20/98 Chen 451 9 SND 08/09/96 5,859,975 01/12/99 Brewer et al. 200,43 395 Sno 03/23/99 6,389,491 05/14/02 Jacobson et al. 5nd 710 62 FOREIGN PATENT DOCUMENTS DATE COUNTRY CLASS SUBCLASS **EXAMINER'S** PATENT NO. Translation INITIALS $\overline{\mathbf{X}}$ 09/20/00 GB 2 347 885 A Sni 03/08/01 wo X WO 01/15865 A1 12/ OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) October 15, 2002. International Search Report prepared by the European Patent Office for 5h 0 PCT/US02/19062. DATE CONSIDERED **EXAMINER**

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